# PCT NEWSLETTER

PATENT COOPERATION TREATY



World Intellectual Property Organization

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### **New PCT Contracting State**

# Libyan Arab Jamahiriya (country code: LY)

On 15 June 2005, the Libyan Arab Jamahiriya deposited its instrument of accession to the PCT, and on 15 September 2005, will become bound by the PCT. Consequently, any international application filed on or after 15 September 2005 will automatically include the designation of the Libyan Arab Jamahiriya. Also, because the Libyan Arab Jamahiriya will be bound by Chapter II of the PCT, it will automatically be elected in any demand filed in respect of an international application filed on or after 15 September 2005. Furthermore, nationals and residents of the Libvan Arab Jamahiriya will be entitled, as from 15 September 2005, to file international applications under the PCT.

# The International Bureau Begins Electronic Processing of PCT Applications

The International Bureau (IB) has begun processing certain PCT applications in a fully electronic manner. Electronic processing means that no paper file will be established at the IB and the record copies and all subsequent documents for these applications will either be scanned on receipt (if received on paper) or will be loaded directly into an electronic dossier (E-dossier) if received electronically. This step represents a significant advance over the partial electronic functionality already in operation within the PCT following the introduction of electronic filing of PCT applications with certain PCT receiving Offices.

Full electronic processing began on 20 June 2005 for PCT applications received from the Korean Intellectual Property Office as receiving Office, and on 4 July 2005 for PCT applications received from the National Board of Patents and Registration of Finland as receiving Office.

The International Bureau will be gradually deploying fully electronic processing in respect of applications received from other PCT receiving Offices during the coming months. The move to electronic processing by the IB is anticipated to facilitate longer term efficiency gains and improved services at the IB, including an online file inspection service, by building up a comprehensive database of PCT-related documents in electronic form.

# Most Frequent PCT Users in 2004

In 2004, 235 applicants accounted for 37,217 (33.1%) of the 112,558 international applications published, each of them with 50 or

#### Inside this issue



The Smart Patenting Solution

www.wipo.int/pct/en

# Selection of PCT Materials on the Internet (www.wipo.int/pct/en/)

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#### **PCT-SAFE**

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- About the Treaty
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- PCT International Search and International Preliminary Examination Guidelines
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- Reservations and incompatibilities
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#### PCT Gazette

PCT news (including the PCT Newsletter, PCT-related Press Releases and Updates and PCT statistics)

Seminar calendar and seminar materials PCT meetings

- PCT Assembly and various committees PCT Reform

The History of the PCT Regulations PCT gallery of notable inventions and inventors Collection of PCT user strategies

#### **PCT Information Service**

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www.wipo.int/pct/en/newslett/index.htm

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more applications published. Of these 235 applicants, 183 were from one of the following three countries: the United States of America (39.1% of the total), Japan (25.5%), and Germany (13.2%). There were 97 applicants in each of whose names 100 or more international applications were published. Koninklijke Philips Electronics N.V. was, for the fourth consecutive year, the largest PCT user, with 2,697 international applications published, followed by Matsushita Electric Industrial Co. Ltd. (1,415) and Siemens Aktiengesellschaft (1,252).

Note that the list of most frequent PCT users contains only the first-named applicants in the applications concerned, and is based on the country of residence of that applicant. Note also that certain legal entities are listed separately from other legal entities with which they may be affiliated (for example: Unilever N.V. (NL) and Unilever plc (GB)).

The list on pages 9 to 14 indicates the applicants by the number of applications published. A second list on pages 15 to 20 indicates the applicants in alphabetical order.

### **Power of Attorney Waiver**

# Notification under PCT Rules 90.4(d) and 90.5(c) (Canadian Intellectual Property Office)

For background information on the abovementioned notification, see *PCT Newsletter* No. 01/2004, page 2.

The Canadian Intellectual Property Office, in its capacities as receiving Office, International

### Reminder

The national Offices of the following States do not yet apply the 30-month time limit for entering the national phase under Chapter I as fixed in PCT Article 22(1) (as modified with effect from 1 April 2002). Note, however, that in respect of the *regional* designation of all those States, the time limit under PCT Article 22(3) of 31 months applies.

CH Switzerland

LU Luxembourg

SE Sweden

TZ United Republic of Tanzania

UG Uganda ZM Zambia

A list of time limits applicable for each designated/ elected Office for entering the national phase under Chapters I and II of the PCT is available at:

www.wipo.int/pct/en/access/legal\_text.htm

Searching Authority and International Preliminary Examining Authority has informed the International Bureau that it waives the requirement under PCT Rule 90.4(b) and 90.5(a)(ii) to submit a separate power of attorney and/or a copy of a general power of attorney. Particular instances in which a separate power of attorney or a copy of a general power of attorney is required are as follows:

Where an agent or a common representative who is not indicated on the Request Form at the time of filing performs any action after filing; or where it is unclear that an agent or common representative has power to act on behalf of the applicant.

(Updating of PCT Applicant's Guide, Vol. I/B, Annex C (CA) and of the table published in PCT Newsletter No. 12/2004 – an updated version of that table is available at www.wipo.int/pct/en/texts/pdf/p\_a\_waivers.pdf)

### **PCT Information Update**

### DZ Algeria (fees)

The amounts of the following national fees, payable to the Algerian National Institute of Industrial Property as designated (or elected) Office, have changed:

filing fee and maintenance

fee for the 1st year: DZD 7,500

fee for priority claim,

per priority: DZD 2,000

publication fee: DZD 5,000

 surcharge for each set of 5 pages in

> excess of 10: DZD 1,200

maintenance fee:

from the 2<sup>nd</sup> to the 5<sup>th</sup>

year, per year: DZD 5,000

(Updating of PCT Applicant's Guide, Vol. II/B, National Chapter, Summary (DZ))

### FI Finland (fees)

The amount of the following fee, payable to the National Board of Patents and Registration of Finland as receiving Office, has changed:

fee for priority document: **EUR 15** 

(Updating of PCT Applicant's Guide, Vol. I/B, Annex C (FI))

### **GB** United Kingdom (institutions with which deposits of microorganisms and other biological material may be made)

The address of the National Collection of Type Cultures (NCTC), an international depositary authority under the Budapest Treaty on the International Recognition of the Deposit of Microorganisms for the Purposes of Patent Procedure, has changed, as follows:

National Collection of Type Cultures (NCTC) **HPA Centre for Infections** 61 Colindale Avenue London NW9 5HT United Kingdom

(Updating of PCT Applicant's Guide, Vol. I/B, Annex L)

### PT Portugal (fees)

The amounts of the following fees, payable to the National Institute of Industrial Property (Portugal) as receiving Office have changed:

transmittal fee: see Table I(a)

fee for priority document: EUR 37.03

The amounts of the following national fees. payable to the Office as designated (or elected) Office, have changed:

for patent:

filing fee: EUR 116.36

EUR 211.56 examination fee:

fee for the submission of each application or

document: **EUR** 5.29

for utility model:

EUR 116.36 filing fee: EUR 211.56 examination fee:

fee for the submission of

each application or

document: **EUR** 5.29

(Updating of PCT Applicant's Guide, Vol. I/B, Annex C (PT), and Vol. II/D, National Chapter, Summary (PT))

### RU Russian Federation (telephone number, e-mail and Internet addresses; requirements concerning agent)

The Federal Service on Intellectual Property, Patents and Trademarks (Russian Federation) has changed its general telephone number

and one of its e-mail addresses, has introduced additional e-mail and Internet addresses and has deleted its teleprinter address. The general telephone number, e-mail and Internet addresses are now as follows:

telephone: (70-95) 956 81 09 (general)

e-mail: rospatent@rupto.ru

fips@rupto.ru

Internet: www.rupto.ru

www.fips.ru

In addition, there has been a change in the requirements as to who can act as agent before the Office as receiving Office, as follows:

who can act as agent?

any patent attorney registered to practice before the Office or another representative having a power of attorney from the applicant.

(Updating of *PCT Applicant's Guide*, Vol. I/A, Annex B1 (RU)) and Vol. I/B, Annex C (RU))

# US United States of America (telephone number; fees)

The telephone number of the PCT Help Desk of the United States Patent and Trademark Office has changed, as follows:

telephone: (1-571) 272 43 00

The components and the wording of the following national fees, payable to the United States Patent and Trademark Office as designated (or elected) Office, have changed, a new search fee has been added and one of the examination fees has changed (other fees not indicated have not changed; amounts in parentheses are applicable in case of filing by a "small entity"):

### search fee:

 IPER prepared by the IPEA/US or the written opinion was prepared by the ISA/US, all claims presented satisfied provisions of PCT Article 33(1)

to (4):

ιο (<del>-</del>).

USD 0 (0)

 search report has been prepared by an ISA other than the US and is provided or has been previously communicated by the

IB to the USPTO: [no change]

#### examination fee:

 IPER prepared by the IPEA/US or the written opinion was prepared by the ISA/US, all claims presented satisfied provisions of PCT

Article 33(1) to (4): USD 0 (0)

(Updating of *PCT Applicant's Guide*, Vol. I/A, Annex B1 (US) and Vol. II/D, National Chapter, Summary (US))

# Search fee (Australian Patent Office, Korean Intellectual Property Office)

As from 1 August 2005, there will be a change in the equivalent amount payable in CHF for an international search carried out by the Australian Patent Office, as indicated in Table I(b).

Further to the announcement published in *PCT Newsletter* No. 06/2005 that the Intellectual Property Office of New Zealand, in its capacity as receiving Office, had specified the Korean Intellectual Property Office (in addition to other Offices) as a competent International Searching and Preliminary Examining Authority, an equivalent amount in NZD has been established for the search fee for an international search by the Korean Intellectual Property Office. The new amount, applicable since 1 June 2005, is indicated in Table I(b).

(Updating of *PCT Applicant's Guide*, Vol. I/B, Annex D (AU and KR))

# Fees relating to the international search (European Patent Office)

The European Patent Office (EPO) has changed the conditions for refund of the search fee, and the extent to which the search fee shall be refunded when the Authority benefits from a European search report that has been established on an application, the priority of which is claimed in an international application filed on or after 1 July 2005, as follows:

conditions for refund and amount of refund of the search fee (other conditions not indicated have not changed):

extent to which the search fee shall be refunded when the Authority benefits from an earlier search in carrying out international search:

for a European search (EPC Art. 78(2)):
 (international application filed on or after 1 July 2005):

(full benefit) EUR 960 (partial benefit) EUR 240

for a European search (EPC Art. 78(2)):
 (international applications filed

before 1 July 2005):

(full benefit) EUR 690 (partial benefit) EUR 172.50

[no change]

[no change]

[no change]

[no change]

for a search (without written opinion)
 on a national application made on
 behalf of a national Office
 (BE, FR, LU, NL, TR)

(full benefit) [no change] (partial benefit) [no change]

(Updating of *PCT Applicant's Guide*, Vol. I/B, Annex D (EP))

# Preliminary examination fee (National Board of Patents and Registration (Finland))

As from 15 July 2005 there will be a change in the amount payable in EUR for an international preliminary examination carried out by the National Board of Patents and Registration (Finland), as indicated in Table II. The additional international preliminary examination fee will also change and will be the same amount as the above-mentioned fee (EUR 550).

## **PCT-SAFE Update**

# Release of new version of the PCT-SAFE Client software

A new version of the PCT-SAFE Client software (version 3.50 (build 0002.173)), dated 15 June 2005, may be downloaded from the PCT-SAFE website at:

www.wipo.int/pct-safe/en/support/download\_client.htm

This version includes information on San Marino (SM) as receiving Office, Latvia (LV) as a new EPO member State (effective 1 July 2005), updated fee schedules, where relevant, and other PCT updates.

# New/Updated PCT Materials on the Internet

(PCT homepage: www.wipo.int/pct/en/)

# The International Patent System in 2004 – Yearly Review of the PCT

The International Patent System in 2004 – Yearly Review of the PCT is now available on the PCT website in Arabic, Chinese, German, Japanese and Russian (in addition to the English version) at, respectively:

www.wipo.int/ar/pct/activity/pct\_2004.pdf www.wipo.int/cn/pct/activity/pct\_2004.pdf www.wipo.int/pct/de/activity/pct\_2004.pdf www.wipo.int/ja/pct/activity/pct\_2004.pdf

www.wipo.int/ru/pct/activity/pct 2004.pdf

The French and Spanish versions will follow shortly.

# Consolidated table of power of attorney waivers

The table showing the PCT Office/Authorities which have notified WIPO that they have waived the requirement to submit a power of attorney under PCT Rule 90.4(b) and/or Rule 90.5(a)(ii) (which was last published in PCT Newsletter No. 12/2004) has been updated and is available on the PCT website at:

www.wipo.int/pct/en/texts/pdf/p\_a\_waivers.pdf

#### Seminar materials

PCT seminar materials are now available in Chinese at:

www.wipo.int/pct/en/seminar/mat.htm

# Spanish translation of Receiving Office Guidelines

The Spanish translation of the Receiving Office Guidelines, as in force from 1 January 2004, is now available in PDF format on the PCT website at:

www.wipo.int/pct/es/texts/pdf/ro.pdf

# PCT Gallery of Notable Inventions and Inventors

The following entry has been made in the gallery of notable inventions (www.wipo.int/pct/en/inventions/inventions.html):

• Google

The following inventors have been added to the gallery of notable inventors (www.wipo.int/pct/en/inventions/inventors/index.html):

- Alec Jeffreys
- Randice-Lisa Altschul

Suggestions for additions to the PCT gallery should be sent to the following e-mail address: pct.infoline@wipo.int

#### **PCT forms**

PCT/RO/134 (Indications relating to deposited microorganism or other biological material) is now available in German, in editable PDF format, at:

www.wipo.int/pct/en/forms/index.htm

# Reminder: Warning About Requests for Payment of Fees

Further to the warnings that were published in PCT Newsletter Nos. 09/2002, 09/2003 ("Practical Advice") and 07/2004, it has come to our attention that PCT applicants and agents are continuing to receive invitations to pay fees that do not come from the International Bureau of WIPO and are unrelated to the processing of international applications under the PCT. Whatever registration services might be offered in such invitations, they bear no connection to WIPO or to any of its official publications. The invitations often identify a particular PCT application by its international publication number (for example: WO 04 xxxxxx), publication date, title of the invention, international application number, priority information and IPC symbols.

The invitations typically refer to a payment, which is to be made in euro or US dollars, by cheque and/or money transfer to an address in Germany or Switzerland. The invitations appear to come from different sources – the ones we have been informed about have come from:

"CPD – Central Patent Database" (new source added to the PCT website on 22 June 2005)

"Register of International Patents"

"Register of International Patent Bulletin/ Registre des données bulletin europeén des brevetes"

"Institut of Commerce for Industry, Trade, Commerce/Wirtschaftsinstitut für Industrie, Handel, Handwerk AG"

"Central Data – Register of International Patents"

Examples of the invitations from these sources are available on the PCT website at:

www.wipo.int/pct/en/warning/ pct\_warning.htm

PCT applicants and agents should note that it is the International Bureau of WIPO alone which publishes all PCT applications promptly after the expiration of 18 months from the priority date (see PCT Article 21(2)(a)); there is no separate fee for such international publication, and the legal effects of international publication are set out in PCT Article 29. In case of doubt in relation to such an invitation, please contact the PCT Information Service at WIPO:

telephone: (41-22) 338 83 38

fax: (41-22) 338 83 39

e-mail: pct.infoline@wipo.int

# Information on the European Regional Phase

### **Extended European Search Report**

The European Patent Office (EPO) has amended the implementing Regulations to the European Patent Convention (EPC) with the result that an extended European search report (EESR) will be issued, as from 1 July 2005, in respect of all direct European patent applications and international applications entering the European Regional phase, filed on or after 1 July 2005. Note that if the EPO acted as International Searching Authority, no supplementary European search report will be drawn up on entry into the European regional phase.

The text of the new EPC Rule concerned (Rule 44a "Extended European search report"), reads as follows:

- "(1) The European search report shall be accompanied by an opinion on whether the application and the invention to which it relates seem to meet the requirements of this Convention, unless a communication under Rule 51, paragraph 2 or paragraph 4, can be issued.
- "(2) The opinion under paragraph 1 shall not be published together with the search report."

By Decision of the Administrative Council of 10 June 2005, the fee for a supplementary European search on an international application for which the international search report was drawn up by the Austrian Patent Office, or in accordance with the Protocol on Centralisation by the National Board of Patents and Registration of Finland, by the Spanish Patent and Trademark Office or by the Swedish Patent and Registration Office will be reduced by EUR 810.

The fee reduction applicable where the ISR was drawn up by a PCT Authority other than those mentioned above will be decided by the Administrative Council in due course.

For further information see:

www.european-patent-office.org/epo/president/e/2005\_06\_30\_d\_e.htm

### **Practical Advice**

# Requesting the recording of changes during the international and national phases

Q: I am an agent acting on behalf of an applicant who has filed several international applications which are at various stages of the international or national phase. I wish to request the recording of a change of address for the applicant. Where should I send my request to? Can I group my request in one single letter sent in respect of all international applications concerned?

A: First of all, you mention that some of your applications have entered the national phase. One important thing that you should be aware of is that the time limit for requesting the recording of changes\* is, according to PCT

Rule 92*bis*.1(b), 30 months from the priority date. Any such requests received after the expiration of that time limit in respect of a particular international application will not be recorded in respect of that application. Therefore, for those international applications that have already entered the national phase, that time limit has probably already expired. Changes to applications which fall into that category will not be recorded by the International Bureau (IB) and you (or the competent agent in the national phase) will have to inform, separately, each designated or elected Office of the change direct.

For those international applications for which the time limit of 30 months from the priority date has not yet expired, you should, preferably, send your request for recording the change direct to the IB. Although letters requesting the recording of changes can be sent via the receiving Office, it is preferable to send the letter direct to the IB, as the receiving Office will in any case forward the request for recording a change to the IB, but it is the date of receipt at the IB of that request that will determine whether or not the change will be recorded under PCT Rule 92bis. It is better if the request for recording the change arrives at the IB as early as possible, particularly if the above-mentioned time limit of 30 months from the priority date is close to expiration in respect of any of the applications. Also, if any of the applications concerned are due to be published shortly and you wish the change to be reflected in the international publication, the letter should reach the IB before the technical preparations of the international publication have been completed, which usually takes place 15 days before the date of the international publication. In the latter two cases, it is particularly advisable to send the request for recording the change by fax to the general PCT fax number: +41-22 338 82 70.

The IB (including the IB as receiving Office) will accept a single letter requesting a change concerning multiple applications provided that the letter contains a list of each international application number affected by the change. Note, however, that not all receiving Offices may be prepared to accept a request for recording a change in such a form, and may require multiple letters (another reason for sending your request direct to the IB).

Rest assured that, whoever the letter is sent to, the IB will, provided that the request for recording the change is received within the applicable time limit, notify all PCT Offices and Authorities interested in the change accordingly, including, in the case where a demand for international preliminary examination has been filed and the international preliminary examination report has not yet been established, the International Preliminary Examining Authority.

Do not be worried if you do not receive confirmation of the recording of the change in respect of all international applications concerned at the same time – at the IB different international applications are dealt with by different formality examiners, and so you may receive more than one confirmation if several applications are concerned.

Note that even though this subject has been dealt with already in earlier issues – see the "Practical Advice" in PCT *Newsletter* Nos. 08/2000\*\*, 05/2002 and 08/2002 – we felt that it is useful to remind applicants about some of the procedure as some applicants have experienced problems because their letters have not been received by the IB until after the time limit under PCT Rule 92*bis* – they should be aware that it is more efficient to submit their requests for recording of a change direct to the IB.

- \* Changes which may be recorded under PCT Rule 92*bis* are: changes in the person, name or address of the applicant, agent, common representative or inventor, or in the residence or nationality of the applicant.
- \*\* Note that the time limit under PCT Rule 92*bis*.1(b) has changed since the publication of this practical advice, but other information remains relevant.

Most Frequent PCT Users\*
(applicants with the most international applications published in 2004)

Rank	Applicant	Country of residence	No. published in 2004
1.	Koninklijke Philips Electronics N.V.	NL	2,697
2.	Matsushita Electric Industrial Co. Ltd.	JP	1,415
3.	Siemens Aktiengesellschaft	DE	1,252
4.	Fujitsu Ltd.	JP	970
5.	Robert Bosch GmbH	DE	791
6.	Sony Corp.	JP	753
7.	Nokia Oyj	FI	733
8.	Motorola, Inc.	US	618
9.	BASF Aktiengesellschaft	DE	588
10.	Bayer	DE + others	548
11.	3M Innovative Properties Co.	US	525
12.	DaimlerChrysler AG	DE	491
13.	Infineon Technologies AG	DE	461
14.	Intel Corp.	US	459
15.	International Business Machines Corp.	US	425
16.	Qualcomm Inc.	US	407
17.	E.I. Du Pont de Nemours and Co.	US	395
18.	Thomson Licensing S.A.	FR	392
19.	Honeywell International Inc.	US	380
20.	Kimberly-Clark Worldwide, Inc.	US	379
21.	The Procter & Gamble Co.	US	367
22.	Telefonaktiebolaget LM Ericsson (publ)	SE	364
23.	Philips Intellectual Property & Standards GmbH	DE	357
24.	Mitsubishi Denki Kabushiki Kaisha	JP	344
25.	Sharp Kabushiki Kaisha	JP	306
26.	LG Electronics Inc.	KR	305
27.	Samsung Electronics Co. Ltd.	KR	292
28.	Scimed Life Systems, Inc.	US	279
29.	The Regents of the University of California	US	278
30.	Medtronic, Inc.	US	264
31.	AstraZeneca AB	SE	254
32.	Japan Science and Technology Agency	JP	253
33.	Tokyo Electron Ltd.	JP	237
34.	Canon Kabushiki Kaisha	JP	222
35.	NEC Corp.	JP	221

<sup>\*</sup> The list contains the first-named applicants in 50 or more international applications published in 2004. Note that certain legal entities may be listed separately from other legal entities with which they may be affiliated.

Rank	Applicant	Country of residence	No. published in 2004
36.	Novartis AG	CH	220
37.	SAP AG	DE	193
38.	General Electric Co.	US	191
39.	BSH Bosch und Siemens Hausgeräte GmbH	DE	187
40.	Centre National de la Recherche Scientifique (C.N.R.S.)	FR	185
41.	Merck & Co. Inc.	US	182
	Unilever plc	GB	182
43.	National Institute of Advanced Industrial Science and Technology	JP	176
44.	Glaxo Group Ltd.	GB	174
45.	Commissariat à l'Énergie Atomique (CEA)	FR	173
	TDK Corp.	JP	173
47.	Council of Scientific and Industrial Research	IN	172
	Pfizer Products Inc.	US	172
49.	Fraunhofer-Gesellschaft zur Förderung der Angewandten Forschung e.V.	DE	171
50.	Henkel KGaA	DE	167
	Seiko Epson Corp.	JP	167
52.	DSM IP Assets B.V.	NL	166
53.	Ciba Specialty Chemicals Holding Inc.	CH	164
54.	Hewlett-Packard Development Company, LP	US	162
55.	Freescale Semiconductor, Inc.	US	156
56.	Bristol-Myers Squibb Co.	US	155
57.	Nikon Corp.	JP	154
58.	Merck Patent GmbH	DE	151
59.	Dow Global Technologies Inc.	US	150
60.	Toyota Jidosha Kabushiki Kaisha	JP	148
61.	Shell Internationale Research Maatschappij B.V.	NL	147
62.	Applied Materials, Inc.	US	146
63.	Daikin Industries, Ltd.	JP	144
64.	Advanced Micro Devices, Inc.	US	139
	Huawei Technologies Co., Ltd.	CN	139
66.	Cisco Technology, Inc.	US	137
67.	Interdigital Technology Corp.	US	134
68.	Olympus Corp.	JP	133
69.	Exxonmobil Chemical Patents Inc.	US	132
	Halliburton Energy Services, Inc.	US	132
	Sony Ericsson Mobile Communications AB	SE	132
72.	Bridgestone Corp.	JP	129
	Pharmacia Corp.	US	129
74.	Baker Hughes Inc.	US	128
75.	F. Hoffmann-La Roche AG	CH	126

Rank	Applicant	Country of residence	No. published in 2004
76.	Showa Denko K.K.	JP	122
77.	Honda Motor Co. Ltd.	JP	121
	Kabushiki Kaisha Toshiba	JP	121
79.	Wyeth	US	117
80.	Nortel Networks Ltd.	CA	116
81.	Sanyo Electric Co. Ltd.	JP	115
82.	Warner-Lambert Co. LLC	US	114
83.	Raytheon Co.	US	112
84.	France Telecom S.A.	FR	109
	Isis Pharmaceuticals, Inc.	US	109
	Kaneka Corp.	JP	109
	Mitsubishi Chemical Corp.	JP	109
	Pharmacia & Upjohn Co.	US	109
89.	Unilever N.V.	NL	108
90.	Asahi Glass Company, Ltd.	JP	107
91.	Colgate-Palmolive Co.	US	106
92.	INA-Schaeffler KG	DE	105
	Ranbaxy Laboratories Ltd.	IN	105
	Smithkline Beecham Corp.	US	105
95.	Continental Teves AG & Co. OHG	DE	104
	Thales Ultrasonics SAS	FR	104
97.	Degussa AG	DE	100
98.	Metso Paper, Inc.	FI	99
	Sun Microsystems, Inc.	US	99
100.	Corning Inc.	US	97
	Hitachi, Ltd.	JP	97
	L'Oréal	FR	97
	Massachusetts Institute of Technology	US	97
	NSK Ltd.	JP	97
105.	Eastman Kodak Co.	US	96
106.	Board of Regents, the University of Texas System	US	95
	Hamamatsu Photonics K.K.	JP	95
	ZF Friedrichshafen AG	DE	95
109.	Novo Nordisk A/S	DK	93
110.	Sumitomo Chemical Company, Ltd.	JP	91
111.	Takeda Pharmaceutical Co. Ltd.	JP	90
	The Government of the United States of America, as represented by the Secretary, Department of Health and Human Services	US	90
113.	Akzo Nobel N.V.	NL	89
	Behr GmbH & Co. KG	DE	89
	Born Gribin & Go. 10		

Rank	rrequent PCT users (2004), continued] Applicant	Country of	No. published
Naiik	Аррисанс	residence	in 2004
116.	L'Air Liquide - Société Anonyme à Directoire et Conseil de Surveillance pour l'Étude et l'Exploitation des Procédés Georges Claude	FR	87
	Renault S.A.S.	FR	87
118.	Sumitomo Electric Industries, Ltd.	JP	86
119.	Aventis Pharma Deutschland GmbH	DE	85
	IGT	US	85
	Qinetiq Ltd.	GB	85
122.	Nippon Steel Corp.	JP	83
123.	Janssen Pharmaceutica N.V.	BE	82
	Koenig & Bauer Aktiengesellschaft	DE	82
	Research in Motion Ltd.	CA	82
126.	Becton, Dickinson and Co.	US	81
	Semiconductor Energy Laboratory Co. Ltd.	JP	81
	Société de Technologie Michelin	FR	81
129.	Ebara Corp.	JP	80
	Giesecke & Devrient GmbH	DE	80
	Nippon Sheet Glass Co. Ltd.	JP	80
	The Boeing Co.	US	80
133.	Advantest Corp.	JP	79
	NGK Insulators, Ltd.	JP	79
135.	Abbott Laboratories	US	78
	Mitsui Chemicals, Inc.	JP	78
137.	Arizona Board of Regents acting for and on behalf of Arizona State University	US	77
	Kao Corp.	JP	77
	Matsushita Electric Works, Ltd.	JP	77
	Molex Inc.	US	77
	SDGI Holdings, Inc.	US	77
142.	Volkswagen AG	DE	76
143.	The General Hospital Corp.	US	75
144.	Baxter International Inc.	US	74
	Eli Lilly and Co.	US	74
146.	Applera Corp.	US	73
	Idemitsu Kosan Co. Ltd.	JP	73
	Micron Technology, Inc.	US	73
	Riken	JP	73
150.	Delphi Technologies, Inc.	US	72
	Ricoh Company, Ltd.	JP	72
152.	University of Florida	US	71
153.	British Telecommunications Plc	GB	70
	The Johns Hopkins University	US	70
155.	Autoliv Development AB	SE	69

Rank	Applicant	Country of residence	No. published in 2004
	Boehringer Ingelheim International GmbH	DE	69
	Exxonmobil Research and Engineering Co.	US	69
	Rhodia Chimie	FR	69
	Tetra Laval Holdings & Finance S.A.	CH	69
160.	Outokumpu Oyj	FI	68
	PPG Industries Ohio, Inc.	US	68
162.	Ajinomoto Co. Inc.	JP	67
163.	Alstom Technology Ltd.	CH	66
	Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO	NL	66
	Pioneer Corp.	JP	66
166.	Avery Dennison Corp.	US	65
	Sony Electronics Inc.	US	65
168.	Bayerische Motoren Werke Aktiengesellschaft	DE	64
	Volvo Lastvagnar AB	SE	64
170.	America Online, Inc.	US	63
	Analog Devices, Inc.	US	63
	Bausch & Lomb Inc.	US	63
	Boehringer Ingelheim Pharma GmbH & Co. KG	DE	63
	Consejo Superior de Investigaciones Científicas	ES	63
	Incyte Corp.	US	63
	Kyowa Hakko Kogyo Co. Ltd.	JP	63
	Milliken & Co.	US	63
178.	General Motors Corp.	US	62
	JSR Corp.	JP	62
	Mars, Inc.	US	62
	Yissum Research Development Co. of the Hebrew University of Jerusalem	IL	62
182.	Casio Computer Co. Ltd.	JP	61
	Endress+Hauser GmbH+Co. KG	DE	61
	Genentech, Inc.	US	61
	Nestec S.A.	CH	61
	The Trustees of Columbia University in the City of New York	US	61
187.	Electronic Data Systems Corp.	US	60
	Lockheed Martin Corp.	US	60
	SMS Demag AG	DE	60
	Yamaha Hatsudoki Kabushiki Kaisha	JP	60
191.	Arkray, Inc.	JP	59
	Johnson Controls Technology Co.	US	59
193.	Dow Corning Corp.	US	58
	Roche Diagnostics GmbH	DE	58
195.	Exelixis, Inc.	US	57

Harris Corp. Schering AG DE  198. Altana Pharma AG DE Carl Zeiss SMT AG Commonwealth Scientific and Industrial Research Organisation AU  201. Novozymes A/S Otis Elevator Co. Pirelli & C. S.P.A. IT  204. California Institute of Technology Chevron U.S.A. Inc. US Daicel Chemical Industries, Ltd. General Instrument Corp. US US US US US US US US US	57 56 56 56 55 55 55 54 54 54
198. Altana Pharma AG Carl Zeiss SMT AG Commonwealth Scientific and Industrial Research Organisation  AU  201. Novozymes A/S Otis Elevator Co. US Pirelli & C. S.P.A. IT  204. California Institute of Technology Chevron U.S.A. Inc. US Daicel Chemical Industries, Ltd.	56 56 55 55 55 55 54 54
Carl Zeiss SMT AG Commonwealth Scientific and Industrial Research Organisation  AU  201. Novozymes A/S Otis Elevator Co. US Pirelli & C. S.P.A.  IT  204. California Institute of Technology Chevron U.S.A. Inc. US Daicel Chemical Industries, Ltd.	56 56 55 55 55 54 54 54
Commonwealth Scientific and Industrial Research Organisation  201. Novozymes A/S Otis Elevator Co. US Pirelli & C. S.P.A. IT  204. California Institute of Technology Chevron U.S.A. Inc. US Daicel Chemical Industries, Ltd.	56 55 55 55 54 54 54
201. Novozymes A/S Otis Elevator Co. US Pirelli & C. S.P.A. IT 204. California Institute of Technology Chevron U.S.A. Inc. US Daicel Chemical Industries, Ltd. JP	55 55 55 54 54 54
Otis Elevator Co.  Pirelli & C. S.P.A.  IT  204. California Institute of Technology Chevron U.S.A. Inc.  US  Daicel Chemical Industries, Ltd.  JP	55 55 54 54 54
Pirelli & C. S.P.A. IT  204. California Institute of Technology Chevron U.S.A. Inc. US  Daicel Chemical Industries, Ltd. JP	55 54 54 54
204. California Institute of Technology Chevron U.S.A. Inc. US Daicel Chemical Industries, Ltd. JP	54 54 54
Chevron U.S.A. Inc.  US  Daicel Chemical Industries, Ltd.  JP	54 54
Daicel Chemical Industries, Ltd. JP	54
General Instrument Corn	54
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LG Chem, Ltd. KR	54
Toray Industries, Inc. JP	54
210. Duke University US	53
Nippon Telegraph and Telephone Corp. JP	53
S. C. Johnson & Son, Inc.	53
Seagate Technology LLC US	53
Teva Pharmaceutical Industries Ltd.	53
The Board of Trustees of the Leland Stanford Junior University US	53
University of Massachusetts US	53
217. Beiersdorf AG DE	52
Conocophillips Co. US	52
Dai Nippon Printing Co. Ltd. JP	52
Lam Research Corp. US	52
Syngenta Participations AG CH	52
222. Bae Systems Information and Electronic Systems Integration Inc. US	51
BEA Systems Inc. US	51
Chiron Corp. US	51
Eveready Battery Company, Inc. US	51
Hitachi Medical Corp. JP	51
Schering Corp. US	51
Yamanouchi Pharmaceutical Co. Ltd. JP	51
Yazaki Corp. JP	51
Zeon Corp. JP	51
231. Invista Technologies S.A.R.L. US	50
Konica Minolta Holdings, Inc.	50
Nissan Motor Co. Ltd. JP	50
Scania CV AB SE	50
Tyco Healthcare Group LP US	50

## **Most Frequent PCT Users\***

(applicants with the most international applications published in 2004) (by alphabetical order of applicants' names)

Rank	Applicant	Country of residence	No. published in 2004
11.	3M Innovative Properties Co.	US	525
135.	Abbott Laboratories	US	78
64.	Advanced Micro Devices, Inc.	US	139
133.	Advantest Corp.	JP	79
162.	Ajinomoto Co. Inc.	JP	67
113.	Akzo Nobel N.V.	NL	89
163.	Alstom Technology Ltd.	CH	66
198.	Altana Pharma AG	DE	56
170.	America Online, Inc.	US	63
170.	Analog Devices, Inc.	US	63
146.	Applera Corp.	US	73
62.	Applied Materials, Inc.	US	146
137.	Arizona Board of Regents acting for and on behalf of Arizona State University	US	77
191.	Arkray, Inc.	JP	59
90.	Asahi Glass Company, Ltd.	JP	107
31.	AstraZeneca AB	SE	254
155.	Autoliv Development AB	SE	69
119.	Aventis Pharma Deutschland GmbH	DE	85
166.	Avery Dennison Corp.	US	65
222.	Bae Systems Information and Electronic Systems Integration Inc.	US	51
74.	Baker Hughes Inc.	US	128
9.	BASF Aktiengesellschaft	DE	588
170.	Bausch & Lomb Inc.	US	63
144.	Baxter International Inc.	US	74
10.	Bayer	DE + others	548
168.	Bayerische Motoren Werke Aktiengesellschaft	DE	64
222.	BEA Systems Inc.	US	51
126.	Becton, Dickinson and Co.	US	81
113.	Behr GmbH & Co. KG	DE	89
217.	Beiersdorf AG	DE	52
106.	Board of Regents, the University of Texas System	US	95
155.	Boehringer Ingelheim International GmbH	DE	69
170.	Boehringer Ingelheim Pharma GmbH & Co. KG	DE	63
72.	Bridgestone Corp.	JP	129
56.	Bristol-Myers Squibb Co.	US	155

<sup>\*</sup> The list contains the first-named applicants in 50 or more international applications published in 2004. Note that certain legal entities may be listed separately from other legal entities with which they may be affiliated.

Rank	Applicant	Country of residence	No. published in 2004
153.	British Telecommunications Plc	GB	70
39.	BSH Bosch und Siemens Hausgeräte GmbH	DE	187
204.	California Institute of Technology	US	54
34.	Canon Kabushiki Kaisha	JP	222
198.	Carl Zeiss SMT AG	DE	56
182.	Casio Computer Co. Ltd.	JP	61
40.	Centre National de la Recherche Scientifique (C.N.R.S.)	FR	185
204.	Chevron U.S.A. Inc.	US	54
222.	Chiron Corp.	US	51
53.	Ciba Specialty Chemicals Holding Inc.	СН	164
66.	Cisco Technology, Inc.	US	137
91.	Colgate-Palmolive Co.	US	106
45.	Commissariat à l'Énergie Atomique (CEA)	FR	173
198.	Commonwealth Scientific and Industrial Research Organisation	AU	56
217.	Conocophillips Co.	US	52
170.	Consejo Superior de Investigaciones Científicas	ES	63
95.	Continental Teves AG & Co. OHG	DE	104
100.	Corning Inc.	US	97
47.	Council of Scientific and Industrial Research	IN	172
217.	Dai Nippon Printing Co. Ltd.	JP	52
204.	Daicel Chemical Industries, Ltd.	JP	54
63.	Daikin Industries, Ltd.	JP	144
12.	DaimlerChrysler AG	DE	491
97.	Degussa AG	DE	100
150.	Delphi Technologies, Inc.	US	72
193.	Dow Corning Corp.	US	58
59.	Dow Global Technologies Inc.	US	150
52.	DSM IP Assets B.V.	NL	166
210.	Duke University	US	53
17.	E.I. Du Pont de Nemours and Co.	US	395
105.	Eastman Kodak Co.	US	96
129.	Ebara Corp.	JP	80
187.	Electronic Data Systems Corp.	US	60
144.	Eli Lilly and Co.	US	74
182.	Endress+Hauser GmbH+Co. KG	DE	61
222.	Eveready Battery Company, Inc.	US	51
195.	Exelixis, Inc.	US	57
69.	Exxonmobil Chemical Patents Inc.	US	132
155.	Exxonmobil Research and Engineering Co.	US	69
75.	F. Hoffmann-La Roche AG	СН	126

Rank	Applicant	Country of residence	No. published in 2004
84.	France Telecom S.A.	FR	109
49.	Fraunhofer-Gesellschaft zur Förderung der Angewandten Forschung e.V.	DE	171
55.	Freescale Semiconductor, Inc.	US	156
4.	Fujitsu Ltd.	JP	970
182.	Genentech, Inc.	US	61
38.	General Electric Co.	US	191
204.	General Instrument Corp.	US	54
178.	General Motors Corp.	US	62
129.	Giesecke & Devrient GmbH	DE	80
44.	Glaxo Group Ltd.	GB	174
69.	Halliburton Energy Services, Inc.	US	132
106.	Hamamatsu Photonics K.K.	JP	95
195.	Harris Corp.	US	57
50.	Henkel KGaA	DE	167
54.	Hewlett-Packard Development Company, LP	US	162
222.	Hitachi Medical Corp.	JP	51
100.	Hitachi, Ltd.	JP	97
113.	Honda Giken Kogyo Kabushiki Kaisha	JP	89
77.	Honda Motor Co. Ltd.	JP	121
19.	Honeywell International Inc.	US	380
64.	Huawei Technologies Co., Ltd.	CN	139
146.	Idemitsu Kosan Co. Ltd.	JP	73
119.	IGT	US	85
92.	INA-Schaeffler KG	DE	105
170.	Incyte Corp.	US	63
13.	Infineon Technologies AG	DE	461
14.	Intel Corp.	US	459
67.	Interdigital Technology Corp.	US	134
15.	International Business Machines Corp.	US	425
231.	Invista Technologies S.A.R.L.	US	50
84.	Isis Pharmaceuticals, Inc.	US	109
123.	Janssen Pharmaceutica N.V.	BE	82
32.	Japan Science and Technology Agency	JP	253
191.	Johnson Controls Technology Co.	US	59
178.	JSR Corp.	JP	62
77.	Kabushiki Kaisha Toshiba	JP	121
84.	Kaneka Corp.	JP	109
137.	Kao Corp.	JP	77
20.	Kimberly-Clark Worldwide, Inc.	US	379
123.	Koenig & Bauer Aktiengesellschaft	DE	82

231. Konica Minolta Holdings, Inc.         JP         50           1. Koninklijke Philips Electronics N.V.         NL         2,697           170. Kyowa Hakko Kogyo Co. Ltd.         JP         63           116. L'Air Liquide - Société Anonyme à Directoire et Conseil de Surveillance pour l'Etude et l'Exploitation des Procédés Georges Claude         FR         87           217. Lan Research Corp.         US         52           204. LG Chem, Ltd.         KR         54           26. LG Electronics Inc.         KR         305           187. Lockheed Martin Corp.         US         60           187. Lockheed Martin Corp.         US         62           100. L'Oréal         FR         97           178. Mars, Inc.         US         62           100. Massaschusetts institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           37. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merck & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         JP         19           100. Milliken & Co.         US	Rank	Applicant	Country of residence	No. published in 2004
170. Kyowa Hakko Kogyo Co. Ltd.         JP         63           116. L'Air Liquide - Société Anonyme à Directoire et Conseil de Surveillance pour l'Étude et l'Exploitation des Procédés Georges Claude         FR         87           217. Lam Research Corp.         US         52           204. L'G Chem, Ltd.         KR         54           26. L'G Electronics Inc.         KR         305           187. Lockheed Martin Corp.         US         62           100. L'Oréal         FR         97           178. Mars, Inc.         US         62           100. Massachusetts Institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           37. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merok & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         63           170. Milliken & Co.         US         63           84. Mitsubishi Chemical Corp.         US         63           84. Mitsubishi Denki Kabushiki Kaisha         JP	231.	Konica Minolta Holdings, Inc.	JP	50
116. L'Air Liquide - Société Anonyme à Directoire et Conseil de Surveillance pour l'Étude et l'Exploitation des Procédés Georges Claude   FR   87   217. Lam Research Corp.   US   52   204. LG Chem, Ltd.   KR   54   26. LG Electronics Inc.   KR   305	1.	Koninklijke Philips Electronics N.V.	NL	2,697
rÉtude et l'Exploitation des Procédés Georges Claude         FR         87           217. Lam Research Corp.         US         52           204. LG Chem, Ltd.         KR         54           204. LG Electronics Inc.         KR         305           187. Lockheed Martin Corp.         US         60           100. L'Oréal         FR         97           178. Mars, Inc.         US         97           100. Massachusetts Institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           137. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merck & Co. Inc.         US         264           41. Merck & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         73           170. Millike & Co.         US         73           40. Mitsubishi Chemical Corp.         JP         109           24. Mitsubishi Denki Kabushiki Kaisha         JP         34           137. Molex Inc.         US	170.	Kyowa Hakko Kogyo Co. Ltd.	JP	63
204. LG Chem, Ltd.         KR         54           26. LG Electronics Inc.         KR         305           187. Lockheed Martin Corp.         US         60           100. L'Oréal         FR         97           178. Mars, Inc.         US         62           100. Massachusetts Institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           137. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merck & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metros Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         73           170. Milliken & Co.         US         63           84. Mitsubishi Chemical Corp.         JP         109           24. Mitsubishi Chemical Kabushiki Kaisha         JP         344           135. Micsui Chemicals, Inc.         US         77           8. Motorola, Inc.         US         618           137. Molex Inc.         US         618           143. National Institute of Advanced Industrial Science and Technology	116.		FR	87
26. LG Electronics Inc.         KR         305           187. Lockheed Martin Corp.         US         60           100. L'Ordal         FR         97           178. Mars, Inc.         US         62           100. Massachusetts Institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           137. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merck & Co. Inc.         US         264           41. Merck & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         73           170. Milliken & Co.         US         63           84. Mitsubishi Chemical Corp.         US         63           84. Mitsubishi Chemical Corp.         JP         78           135. Mitsui Chemicals, Inc.         US         77           137. Molex Inc.         US         77           8. Motorola, Inc.         US         618           43. National Institute of Advanced Industrial Science and Technology         JP </td <td>217.</td> <td>Lam Research Corp.</td> <td>US</td> <td>52</td>	217.	Lam Research Corp.	US	52
187. Lockheed Martin Corp.         US         60           100. L'Oréal         FR         97           178. Mars, Inc.         US         62           100. Massachusetts Institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           137. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merck & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         73           170. Milliken & Co.         US         63           84. Mitsubishi Chemical Corp.         US         63           184. Mitsubishi Chemical Corp.         JP         109           24. Mitsubishi Chemicals, Inc.         JP         344           135. Mitsui Chemicals, Inc.         JP         78           137. Molex Inc.         US         77           8. Motorola, Inc.         US         618           43. National Institute of Advanced Industrial Science and Technology         JP         176           35. NEC Corp.         JP	204.	LG Chem, Ltd.	KR	54
100. L'Oréal         FR         97           178. Mars, Inc.         US         62           100. Massachusetts Institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           137. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merck & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         73           170. Milliken & Co.         US         63           84. Mitsubishi Chemical Corp.         JP         109           24. Mitsubishi Denki Kabushiki Kaisha         JP         344           135. Mitsui Chemicals, Inc.         JP         78           137. Molex Inc.         US         618           43. National Institute of Advanced Industrial Science and Technology         JP         176           35. NEC Corp.         JP         221           163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO         NL         66           162. Nestec S.A.         CH         61	26.	LG Electronics Inc.	KR	305
178. Mars, Inc.         US         62           100. Massachusetts Institute of Technology         US         97           2. Matsushita Electric Industrial Co. Ltd.         JP         1,415           137. Matsushita Electric Works, Ltd.         JP         77           30. Medtronic, Inc.         US         264           41. Merck & Co. Inc.         US         182           58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         73           170. Milliken & Co.         US         63           84. Mitsubishi Chemical Corp.         JP         109           24. Mitsubishi Denki Kabushiki Kaisha         JP         344           135. Mitsu Chemicals, Inc.         JP         78           137. Molex Inc.         US         77           8. Motorola, Inc.         US         77           8. Motorola, Inc.         US         618           43. National Institute of Advanced Industrial Science and Technology         JP         176           35. NEC Corp.         JP         221           163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO         NL         66      <	187.	Lockheed Martin Corp.	US	60
100.       Massachusetts Institute of Technology       US       97         2.       Matsushita Electric Industrial Co. Ltd.       JP       1,415         137.       Matsushita Electric Works, Ltd.       JP       77         30.       Medtronic, Inc.       US       264         41.       Merck & Co. Inc.       US       182         58.       Merck Patent GmbH       DE       151         98.       Metso Paper, Inc.       FI       99         146.       Micron Technology, Inc.       US       73         170.       Milliken & Co.       US       63         84.       Mitsubishi Chemical Corp.       JP       109         24.       Mitsubishi Denki Kabushiki Kaisha       JP       344         135.       Mitsui Chemicals, Inc.       JP       78         137.       Molex Inc.       US       77         8.       Motorola, Inc.       US       618         43.       National Institute of Advanced Industrial Science and Technology       JP       176         35.       NEC Corp.       JP       221         163.       Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. <td>100.</td> <td>L'Oréal</td> <td>FR</td> <td>97</td>	100.	L'Oréal	FR	97
2. Matsushita Electric Industrial Co. Ltd.       JP       1,415         137. Matsushita Electric Works, Ltd.       JP       77         30. Medtronic, Inc.       US       264         41. Merck & Co. Inc.       US       182         58. Merck Patent GmbH       DE       151         98. Metso Paper, Inc.       FI       99         146. Micron Technology, Inc.       US       73         170. Milliken & Co.       US       63         84. Mitsubishi Chemical Corp.       JP       109         24. Mitsubishi Denki Kabushiki Kaisha       JP       344         135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       80         129. Nippon Sheet Glass Co. Ltd.       JP       80         120. Nippon Telegraph and Telephone Corp.       JP       53	178.	Mars, Inc.	US	62
137. Matsushita Electric Works, Ltd.       JP       77         30. Medtronic, Inc.       US       264         41. Merck & Co. Inc.       US       182         58. Merck Patent GmbH       DE       151         98. Metso Paper, Inc.       FI       99         146. Micron Technology, Inc.       US       73         170. Milliken & Co.       US       63         84. Mitsubishi Chemical Corp.       JP       109         24. Mitsubishi Denki Kabushiki Kaisha       JP       344         135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       83         220. Nippon Telegraph and Telephone Corp.       JP       83         231. Nissan Motor Co. Ltd.       JP       50 <t< td=""><td>100.</td><td>Massachusetts Institute of Technology</td><td>US</td><td>97</td></t<>	100.	Massachusetts Institute of Technology	US	97
30. Medtronic, Inc.       US       264         41. Merck & Co. Inc.       US       182         58. Merck Patent GmbH       DE       151         98. Metso Paper, Inc.       FI       99         146. Micron Technology, Inc.       US       73         170. Milliken & Co.       US       63         84. Mitsubishi Chemical Corp.       JP       109         24. Mitsubishi Denki Kabushiki Kaisha       JP       344         135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       77         8. Motorola, Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Steet Glass Co. Ltd.       JP       83         120. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj	2.	Matsushita Electric Industrial Co. Ltd.	JP	1,415
41. Merck & Co. Inc.       US       182         58. Merck Patent GmbH       DE       151         98. Metso Paper, Inc.       FI       99         146. Micron Technology, Inc.       US       73         170. Milliken & Co.       US       63         84. Mitsubishi Chemical Corp.       JP       109         24. Mitsubishi Denki Kabushiki Kaisha       JP       344         135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG<	137.	Matsushita Electric Works, Ltd.	JP	77
58. Merck Patent GmbH         DE         151           98. Metso Paper, Inc.         FI         99           146. Micron Technology, Inc.         US         73           170. Milliken & Co.         US         63           84. Mitsubishi Chemical Corp.         JP         109           24. Mitsubishi Denki Kabushiki Kaisha         JP         344           135. Mitsui Chemicals, Inc.         JP         78           137. Molex Inc.         US         77           8. Motorola, Inc.         US         618           43. National Institute of Advanced Industrial Science and Technology         JP         176           35. NEC Corp.         JP         221           163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO         NL         66           182. Nestec S.A.         CH         61           133. NGK Insulators, Ltd.         JP         79           57. Nikon Corp.         JP         80           122. Nippon Sheet Glass Co. Ltd.         JP         80           122. Nippon Telegraph and Telephone Corp.         JP         53           231. Nissan Motor Co. Ltd.         JP         50           7. Nokia Oyj         FI         733           80. Nortel	30.	Medtronic, Inc.	US	264
98. Metso Paper, Inc.       FI       99         146. Micron Technology, Inc.       US       73         170. Milliken & Co.       US       63         84. Mitsubishi Chemical Corp.       JP       109         24. Mitsubishi Denki Kabushiki Kaisha       JP       344         135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       77         8. Motorola, Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG <td>41.</td> <td>Merck &amp; Co. Inc.</td> <td>US</td> <td>182</td>	41.	Merck & Co. Inc.	US	182
146.       Micron Technology, Inc.       US       73         170.       Milliken & Co.       US       63         84.       Mitsubishi Chemical Corp.       JP       109         24.       Mitsubishi Denki Kabushiki Kaisha       JP       344         135.       Mitsui Chemicals, Inc.       JP       78         137.       Molex Inc.       US       77         8.       Motorola, Inc.       US       618         43.       National Institute of Advanced Industrial Science and Technology       JP       176         35.       NEC Corp.       JP       221         163.       Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182.       Nestec S.A.       CH       61         183.       NGK Insulators, Ltd.       JP       79         57.       Nikon Corp.       JP       80         129.       Nippon Sheet Glass Co. Ltd.       JP       80         120.       Nippon Telegraph and Telephone Corp.       JP       53         231.       Nissan Motor Co. Ltd.       JP       50         7.       Nokia Oyj       FI       733         80.       Nortel Networks Ltd.	58.	Merck Patent GmbH	DE	151
170.       Milliken & Co.       US       63         84.       Mitsubishi Chemical Corp.       JP       109         24.       Mitsubishi Denki Kabushiki Kaisha       JP       344         135.       Mitsui Chemicals, Inc.       JP       78         137.       Molex Inc.       US       618         43.       National Institute of Advanced Industrial Science and Technology       JP       176         35.       NEC Corp.       JP       221         163.       Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182.       Nestec S.A.       CH       61         133.       NGK Insulators, Ltd.       JP       79         57.       Nikon Corp.       JP       80         122.       Nippon Sheet Glass Co. Ltd.       JP       80         122.       Nippon Steel Corp.       JP       53         231.       Nissan Motor Co. Ltd.       JP       50         7.       Nokia Oyj       FI       733         80.       Nortel Networks Ltd.       CA       116         36.       Novartis AG       CH       220	98.	Metso Paper, Inc.	FI	99
84. Mitsubishi Chemical Corp.       JP       109         24. Mitsubishi Denki Kabushiki Kaisha       JP       344         135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       77         8. Motorola, Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	146.	Micron Technology, Inc.	US	73
24. Mitsubishi Denki Kabushiki Kaisha       JP       344         135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       77         8. Motorola, Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	170.	Milliken & Co.	US	63
135. Mitsui Chemicals, Inc.       JP       78         137. Molex Inc.       US       77         8. Motorola, Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	84.	Mitsubishi Chemical Corp.	JP	109
137. Molex Inc.       US       77         8. Motorola, Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	24.	Mitsubishi Denki Kabushiki Kaisha	JP	344
8. Motorola, Inc.       US       618         43. National Institute of Advanced Industrial Science and Technology       JP       176         35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	135.	Mitsui Chemicals, Inc.	JP	78
43. National Institute of Advanced Industrial Science and Technology  35. NEC Corp.  36. NEC Corp.  37. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO  37. Nestec S.A.  38. NGK Insulators, Ltd.  39. Nikon Corp.  30. Nippon Sheet Glass Co. Ltd.  39. Nippon Steel Corp.  30. Nippon Telegraph and Telephone Corp.  30. Nippon Telegraph and Telephone Corp.  30. Nortel Networks Ltd.  31. Nortel Networks Ltd.  32. Novartis AG  33. Novartis AG  34. Novartis AG  35. Novartis AG  36. Novartis AG	137.	Molex Inc.	US	77
35. NEC Corp.       JP       221         163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	8.	Motorola, Inc.	US	618
163. Nederlandse Organisatie voor Toegepast-Natuurwetenschappelijk Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	43.	National Institute of Advanced Industrial Science and Technology	JP	176
Onderzoek TNO       NL       66         182. Nestec S.A.       CH       61         133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	35.	NEC Corp.	JP	221
133. NGK Insulators, Ltd.       JP       79         57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	163.		NL	66
57. Nikon Corp.       JP       154         129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	182.	Nestec S.A.	СН	61
129. Nippon Sheet Glass Co. Ltd.       JP       80         122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	133.	NGK Insulators, Ltd.	JP	79
122. Nippon Steel Corp.       JP       83         210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	57.	Nikon Corp.	JP	154
210. Nippon Telegraph and Telephone Corp.       JP       53         231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	129.	Nippon Sheet Glass Co. Ltd.	JP	80
231. Nissan Motor Co. Ltd.       JP       50         7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	122.	Nippon Steel Corp.	JP	83
7. Nokia Oyj       FI       733         80. Nortel Networks Ltd.       CA       116         36. Novartis AG       CH       220	210.	Nippon Telegraph and Telephone Corp.	JP	53
80. Nortel Networks Ltd. CA 116 36. Novartis AG CH 220	231.	Nissan Motor Co. Ltd.	JP	50
36. Novartis AG CH 220	7.	Nokia Oyj	FI	733
36. Novartis AG CH 220	80.	**	CA	116
	36.		СН	220
	109.	Novo Nordisk A/S		
201. Novozymes A/S DK 55	201.		DK	55
100. NSK Ltd. JP 97		•	JP	97

Rank	Applicant	Country of residence	No. published in 2004
68.	Olympus Corp.	JP	133
201.	Otis Elevator Co.	US	55
160.	Outokumpu Oyj	FI	68
47.	Pfizer Products Inc.	US	172
84.	Pharmacia & Upjohn Co.	US	109
72.	Pharmacia Corp.	US	129
23.	Philips Intellectual Property & Standards GmbH	DE	357
163.	Pioneer Corp.	JP	66
201.	Pirelli & C. S.P.A.	IT	55
160.	PPG Industries Ohio, Inc.	US	68
119.	Qinetiq Ltd.	GB	85
16.	Qualcomm Inc.	US	407
92.	Ranbaxy Laboratories Ltd.	IN	105
83.	Raytheon Co.	US	112
116.	Renault S.A.S.	FR	87
123.	Research in Motion Ltd.	CA	82
155.	Rhodia Chimie	FR	69
150.	Ricoh Company, Ltd.	JP	72
146.	Riken	JP	73
5.	Robert Bosch GmbH	DE	791
193.	Roche Diagnostics GmbH	DE	58
210.	S. C. Johnson & Son, Inc.	US	53
27.	Samsung Electronics Co. Ltd.	KR	292
81.	Sanyo Electric Co. Ltd.	JP	115
37.	SAP AG	DE	193
231.	Scania CV AB	SE	50
195.	Schering AG	DE	57
222.	Schering Corp.	US	51
28.	Scimed Life Systems, Inc.	US	279
137.	SDGI Holdings, Inc.	US	77
210.	Seagate Technology LLC	US	53
50.	Seiko Epson Corp.	JP	167
126.	Semiconductor Energy Laboratory Co. Ltd.	JP	81
25.	Sharp Kabushiki Kaisha	JP	306
61.	Shell Internationale Research Maatschappij B.V.	NL	147
76.	Showa Denko K.K.	JP	122
3.	Siemens Aktiengesellschaft	DE	1,252
92.	Smithkline Beecham Corp.	US	105
187.	SMS Demag AG	DE	60
126.	Société de Technologie Michelin	FR	81

Rank	Applicant	Country of residence	No. published in 2004
6.	Sony Corp.	JP	753
166.	Sony Electronics Inc.	US	65
69.	Sony Ericsson Mobile Communications AB	SE	132
110.	Sumitomo Chemical Company, Ltd.	JP	91
118.	Sumitomo Electric Industries, Ltd.	JP	86
98.	Sun Microsystems, Inc.	US	99
217.	Syngenta Participations AG	CH	52
111.	Takeda Pharmaceutical Co. Ltd.	JP	90
45.	TDK Corp.	JP	173
22.	Telefonaktiebolaget LM Ericsson (publ)	SE	364
155.	Tetra Laval Holdings & Finance S.A.	CH	69
210.	Teva Pharmaceutical Industries Ltd.	IL	53
95.	Thales Ultrasonics SAS	FR	104
210.	The Board of Trustees of the Leland Stanford Junior University	US	53
129.	The Boeing Co.	US	80
143.	The General Hospital Corp.	US	75
	The Government of the United States of America, as represented by the Secretary, Department of Health and Human Services	US	90
153.	The Johns Hopkins University	US	70
21.	The Procter & Gamble Co.	US	367
29.	The Regents of the University of California	US	278
182.	The Trustees of Columbia University in the City of New York	US	61
18.	Thomson Licensing S.A.	FR	392
33.	Tokyo Electron Ltd.	JP	237
204.	Toray Industries, Inc.	JP	54
60.	Toyota Jidosha Kabushiki Kaisha	JP	148
231.	Tyco Healthcare Group LP	US	50
89.	Unilever N.V.	NL	108
41.	Unilever plc	GB	182
152.	University of Florida	US	71
210.	University of Massachusetts	US	53
142.	Volkswagen AG	DE	76
168.	Volvo Lastvagnar AB	SE	64
82.	Warner-Lambert Co. LLC	US	114
79.	Wyeth	US	117
187.	Yamaha Hatsudoki Kabushiki Kaisha	JP	60
222.	Yamanouchi Pharmaceutical Co. Ltd.	JP	51
222.	Yazaki Corp.	JP	51
178.	Yissum Research Development Co. of the Hebrew University of Jerusalem	IL	62
222.	Zeon Corp.	JP	51
106.	ZF Friedrichshafen AG	DE	95

		PCT Seminar Calenda	r			
Dates and location Seminar  18–19 July 2005 Washington (US)  Language of seminar  English		Nature of seminar; WIPO speakers (and others where known)	Organizer and contact numbers  American Intellectual Property Law Association (AIPLA) (Ms. Iris Howell) Tel: (1–703) 415 07 80 Fax: (1–703) 415 07 86 E-mail: aipla@aipla.org Internet (for registration): www.aipla.org			
		Advanced PCT seminar Speaker: Ms. Bidwell (USPTO)				
21–22 July 2005 Minneapolis (US)	English	Advanced PCT seminar WIPO speaker: Mr. Erstling	American Intellectual Property Law Association (AIPLA) (see above)			
25–26 July 2005 San Diego (US)	English	Advanced PCT seminar WIPO speaker: Mr. Erstling	American Intellectual Property Law Association (AIPLA) (see above)			
26 July 2005 Tokyo (JP)	Japanese	Seminar on the PCT system and the Madrid system WIPO speakers: Mr. Nakamaki and Mr. Okutomi	Japan Patent Attorneys Association Tel: (81–3) 35 19 23 60 Fax: (81–3) 35 81 12 05			
27 July 2005 Nagoya (JP)	Japanese	Seminar on the PCT system and the Madrid system WIPO speakers: Mr. Nakamaki and Mr. Okutomi	Japan Patent Attorneys Association Tel: (81–3) 35 19 23 60 Fax: (81–3) 35 81 12 05			
28 July 2005 Osaka (JP)	Japanese	Seminar on the PCT system and the Madrid system WIPO speakers: Mr. Nakamaki and Mr. Okutomi	Japan Patent Attorneys Association Tel: (81–3) 35 19 23 60 Fax: (81–3) 35 81 12 05			
13–14 September 2005 Oslo (NO)	English	PCT seminar WIPO speaker: Mr. Reischle	Norwegian Patent Office (Ms. Åse Skogø) Tel: (47–22) 38 76 17/38 73 00 Fax: (47–22) 38 73 31 E-mail: ask@patentstyret.no			
12–13 October 2005 Helsinki (FI)	English	Advanced PCT seminar WIPO speakers: Mr. H.G. Bartels and Mrs. Coeckelbergs	National Board of Patents and Registration of Finland Tel: (358–9) 69 39 500 Fax: (358–9) 69 39 53 22			
27–28 October 2005 Helsinki (FI)	English	Advanced PCT seminar WIPO speaker: to be announced	Helsinki University of Technology, Lifelong Learning Institute of Dipoli (Ms. Arja Andsten) Tel: (358–9) 451 40 47 Fax: (358–9) 451 40 68 E-mail: arja.andsten@dipoli.hut.fi Internet: www.dipoli.hut.fi			
17–18 November 2005 London (GB)	English	Advanced PCT formalities seminar WIPO speaker: to be announced	Management Forum Ltd Tel: (44–1483) 57 00 99 Fax: (44–1483) 53 64 24 E-mail: josephine.leak@management-forum.co.uk			
8–9 December 2005 London (GB)	English	PCT presentation at the 4 <sup>th</sup> Annual Conference for Senior Patent Administrators WIPO speaker: to be announced	Management Forum Ltd Tel: (44–1483) 57 00 99 Fax: (44–1483) 53 64 24 E-mail: josephine.leak@management-forum.co.uk			
13–14 December 2005 Paris (FR)	French	PCT seminar WIPO speakers: Mr. Genin and Ms. Bonvallet	Institut national de la propriété industrielle (INPI) (Mrs. Christiane Sadrin) Tel: (33–1) 53 04 55 76 Fax: (33–1) 53 04 52 52			

### **PCT Fee Tables**

### (amounts on 1 July 2005, unless otherwise indicated)

The following Tables show the amounts and currencies of the main PCT fees which are payable to the receiving Offices (ROs) and the International Preliminary Examining Authorities (IPEAs) during the international phase under Chapter I (Tables I(a) and I(b)) and under Chapter II (Table II). Fees which are payable only in particular circumstances are not shown; nor are details of certain reductions and refunds which may be available; such information can be found in the *PCT Applicant's Guide*, Vol. I/B, Annexes C, D and E. Note that all amounts are subject to change due to variations in the fees themselves or fluctuations in exchange rates. The international filing fee may be reduced by CHF 100 under certain circumstances where the request is prepared using the PCT-EASY features of the PCT-SAFE software or by CHF 200 or 300 where the international application is filed in electronic form, as prescribed; see footnotes 2 and 5 for details. A 75% reduction in the international filing fee (including the fee per sheet over 30) and the handling fee, as well as an exemption from the transmittal fee payable to the International Bureau as receiving Office, is also available to applicants from certain States—see footnotes 3 and 10. (Note that if the CHF 100, 200 or 300 reduction, as the case may be, and the 75% reduction are applicable, the 75% reduction is calculated *after* the CHF 100, 200 or 300 reduction.) The footnotes to the Fee Tables follow Table II.

#### Key to abbreviations used in fee tables:

eq	equivalent of -	BGL	Bulgarian lev	GBP	Pound sterling	LSM	Lesotho loti	SEK	Swedish krona
IPEA	International Preliminary	BRR	Brazilian real	GEL	Georgian lari	LTL	Lithuanian litas	SGD	Singapore dollar
	Examining Authority	BYR	Belarussian rouble	GHC	Ghanaian cedi	LVL	Latvian lat	SIT	Slovenian tolar
ISA	International Searching	BZD	Belize dollar	HRK	Croatian kuna	MAD	Moroccan dirham	SKK	Slovak koruna
	Authority	CAD	Canadian dollar	HUF	Hungarian forint	MDL	Moldovan leu	TJS	Tajik somoni
n a	not applicable	CHF	Swiss franc	IDR	Indonesian rupiah	MKD	Macedonian denar	TND	Tunisian dinar
RO	receiving Office	CNY	Yuan renminbi	ILS	New Israel shekel	MWK	Malawian kwacha	TTD	Trinidad and Tobago
		COP	Colombian peso	INR	Indian rupee	MXP	Mexican peso		dollar
Curre	ncies:	CUP	Cuban convertible peso	ISK	Icelandic krona	NOK	Norwegian krone	UAH	Ukrainian hryvnia
AED	United Arab Emirates	CYP	Cyprus pound	JPY	Japanese yen	NZD	New Zealand dollar	USD	US dollar
	dirham	CZK	Czech koruna	KES	Kenyan shilling	PHP	Philippine peso	VND	Vietnamese dong
ALL	Albanian lek	DKK	Danish krone	KGS	Kyrgyz som	PLZ	Polish zloty	XAF	CFA franc BEAC
AMD	Armenian dram	DZD	Algerian dinar	KPW	KP won	ROL	Romanian leu	YUD	Yugoslavian dinar
AUD	Australian dollar	EEK	Estonian kroon	KRW	KR won	RUR	Russian rouble	ZAR	South African rand
AZM	Azerbaijani manat	EUR	Euro	KZT	Kazakh tenge	SDP	Sudanese pound	ZWD	Zimbabwe dollar
BAM	Convertible mark								

## Table I(a) — Transmittal and international filing fees

(amounts on 1 July 2005, unless otherwise indicated)

	(amounts on 1 July 2000, unless otherwise mulcateu)										
RO	Transn	nittal fee <sup>1</sup>	fil	ternational ing fee <sup>1, 2, 3</sup> CHF 1,400)	Fee per sheet over 30 <sup>1, 2, 3, 4</sup> (CHF 15)	PCT-EASY reduction <sup>2, 5</sup> (CHF 100)	Competent ISA(s) <sup>6</sup>				
AG	Information	n not yet availal	ole								
AL	ALL	9,000	CHF	1,400	15	n a	EP				
АМ	AMD	32,000	USD	1,211	13	87	EP RU				
AP	USD	50	USD	1,211	13	87	AT EP SE				
	(or eq in lo	cal currency)									
АТ	EUR	50	EUR	902	10	64	EP				
AU	AUD	100	AUD	1,525	16	109	AU				
AZ	AZM	55,000	USD	1,211	13	n a	EP RU				
ВА	BAM	50	EUR	902	10	64	EP				
ВЕ	EUR	40	EUR	902	10	64	EP				
ВG	BGL	60	BGL	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP RU				
BR	BRR	236	BRR	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	AT EP SE US				

Table I(a) — Transmittal and international filing fees [continued] (amounts on 1 July 2005, unless otherwise indicated)

RO Transmittal fee<sup>1</sup> International Fee per sheet **PCT-EASY** Competent over 30<sup>1, 2, 3, 4</sup> filing fee<sup>1, 2, 3</sup> reduction2, 5 ISA(s)6 (CHF 1,400) (CHF 15) (CHF 100) BW Information not yet available ΒY BYR eq USD 70 USD 1,211 13 n a EP RU ΒZ BZD 220 USD 13 87 ΕP 1,211 CA CAD 300 CAD 1,489 16 106 CA 1,400 СН CHF 100 CHF 100 ΕP 15 CNY CN 500 CNY eq CHF 1,400 eq CHF 15 eq CHF 100 CN COP<sup>7</sup> CO COP eq **USD** 1,211 eq **USD** 13 eq **USD** 87 AT, EP, ES, RU CR USD 175 USD 1,211 13 87 **EP ES** CU USD (or eq CUP)200 **USD** (or eq **CUP**) 1,211 13 87 AT EP ES RU CY CYP 75 CYP ΕP 526 6 n a CZ CZK 1,500 CZK eq **CHF** 1,400 eq **CHF** 15 eq CHF 100 ΕP DE **EUR** 90 **EUR** 902 10 64 ΕP 1,500 DKK 70 EP SE DK DKK 6,700 480 Information not yet available DΖ DZD None CHF 1,400 15 100 AT EP EΑ RUR eq USD 50 USD 1,211 13 87 EP RU USD<sup>7</sup> USD EC 1,211 13 87 **EP ES** EE **EEK** 1,800 **EEK** eq CHF 1,400 eq CHF 15 eq CHF 100 EG USD 100 USD AT EP US 1,211 13 87 EP<sup>5</sup> **EUR** 100 **EUR** 902 10 64 ΕP ES<sup>5</sup> **EP ES EUR** 65.27 **EUR** 902 10 64  ${\sf FI}^5$ **EUR** 135 **EUR** 902 10 64 **EP FI SE** FR<sup>5</sup> **EUR** 60 **EUR** 902 ΕP 10 64 GB<sup>5</sup> **GBP** 55 **GBP** 628 7 45 ΕP GD Information not yet available

Table I(a) — Transmittal and international filing fees [continued] (amounts on 1 July 2005, unless otherwise indicated)

RO	Transmittal fee <sup>1</sup>		fi	nternational ling fee <sup>1, 2, 3</sup> CHF 1,400)	Fee per sheet over 30 <sup>1, 2, 3, 4</sup> (CHF 15)	PCT-EASY reduction <sup>2, 5</sup> (CHF 100)	Competent ISA(s) <sup>6</sup>
GE	GEL <sup>8</sup>	10	USD	1,211	13	87	EP RU
GH	GHC <sup>9</sup>	2,500 or 5,000	USD	1,211	13	n a	AT AU CN EP SE
GR	EUR	115	EUR	902	10	64	EP
HR	HRK	200	HRK	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP
HU	HUF	10,000	HUF	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP RU
IB <sup>5</sup>	CHF <sup>10</sup> or EUR <sup>10</sup> or USD <sup>10</sup>	100 64 87	CHF or EUR or USD	1,400 902 1,211	15 10 13	100 64 87	See footnote 11
ID	IDR	500,000	IDR	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	AU EP KR RU
IE	EUR	76.00	EUR	902	10	64	EP
IL	ILS	476	USD	1,211	13	87	EP US
IN	INR 8,000 (filing by indiv: 2,000)		USD	1,211	13	87	AT AU CN EP SE US
IS	ISK 6,500		ISK	74,000	800	5,300	EP SE
IT	EUR	30.99	EUR	902	10	n a	EP
JP <sup>5</sup>	JPY	13,000	JPY	123,200	1,300	8,800	EP JP
KE	USD (or KE	<b>ES</b> equiv)250 mailing	USD	1,211	13	87	AT AU CN EP SE
KG	KGS eq L	JSD 100	USD	1,211	13	87	EP RU
KM	Information	not yet availal	ble			П	
KP	KPW eq (	CHF 50	KPW	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	AT RU
KR <sup>5</sup>	KRW	45,000	KRW	1,195,000	13,000	85,000	AT AU JP <sup>12</sup> KR
KZ	<b>KZT</b> <sup>7</sup>	_	USD	1,211	13	87	EP RU
LR	USD	45	USD	1,211	13	na	AT AU CN EP SE
LS	LSM <sup>7</sup>		LSM	eq <b>CHF</b> 1,400	eq CHF 15	na	AT EP
LT	LTL	320	EUR	902	10	64	EP RU
LU	EUR	19	EUR	902	10	n a	EP
LV	LVL	47.20	EUR	902	10	64	EP RU
MA		None	CHF	1,400	15	na	AT EP RU SE
МС	EUR	49 <sup>13</sup>	EUR	902	10	n a	EP

Table I(a) — Transmittal and international filing fees [continued] (amounts on 1 July 2005, unless otherwise indicated)

RO	Transmittal fee <sup>1</sup>		Transmittal fee <sup>1</sup> International filing fee <sup>1, 2, 3</sup> (CHF 1,400)		ternational ling fee <sup>1, 2, 3</sup>	Fee per sheet over 30 <sup>1, 2, 3, 4</sup> (CHF 15)	PCT-EASY reduction <sup>2, 5</sup> (CHF 100)	Competent ISA(s) <sup>6</sup>
MD	MDL	180	USD	1,211	13	87	EP RU	
MK	MKD	2,700	MKD	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP	
MN		None	CHF	1,400	15	100	EP RU	
MW	MWK	6,000	MWK	111,100	1,200	7,900	EP	
MX	MXP <sup>3</sup> eq	<b>USD</b> 200	MXP	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP ES SE US	
NA	Information	n not yet availat	ole					
NG	Information	n not yet availat	ole					
NI	USD	200	USD	1,211	13	87	EP ES	
NL <sup>5</sup>	EUR	50	EUR	902	10	64	EP	
NO	NOK	500	NOK	7,370	80	530	EP SE	
NZ	NZD	180 <sup>14</sup>	NZD	1,653	18	118	AU EP KR US	
OA	XAF <sup>7</sup>	_	<b>XAF</b> eq <b>CHF</b> 1,400		eq <b>CHF</b> 15	n a	AT EP RU SE	
ОМ	Information	n not yet availal	ole					
PG	Information	n not yet availat	ole					
РН	PHP	3,500	USD	1,211	13	87	AU EP JP KR US	
PL	PLZ	300	PLZ	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	n a	EP	
РТ	EUR	31.73	EUR	902	10	64	EP	
RO	ROL	300,000	CHF	1,400	15	100	AT EP RU	
RU	RUR	294	USD	1,211	13	87	EP RU	
sc	Information	n not yet availat	ole					
SD	SDP	50	SDP	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	n a	EP	
SE	SEK	1,200	SEK	8,140	90	580	EP SE	
SG	SGD	150	SGD	1,926	21	138	AT AU EP	
SI	SIT	22,000	SIT	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP	
sĸ	SKK	2,000	SKK	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP	
SM	EUR	50	EUR	902	10	n a	EP	
SY	USD <sup>7</sup>	_	USD	1,211	13	87	AT EP RU	
TJ	TJS <sup>7</sup>	_	USD	1,211	13	n a	EP RU	
тм	USD <sup>7</sup>	_	USD	1,211	13	87	EP RU	
TN	TND <sup>7</sup>	_	CHF	1,400	15	n a	EP	

# Table I(a) — Transmittal and international filing fees [continued] (amounts on 1 July 2005, unless otherwise indicated)

RO	Transmittal fee <sup>1</sup>		International filing fee <sup>1, 2, 3</sup> (CHF 1,400)		Fee per sheet over 30 <sup>1, 2, 3, 4</sup> (CHF 15)	PCT-EASY reduction <sup>2, 5</sup> (CHF 100)	Competent ISA(s) <sup>6</sup>
TR	CHF	100	CHF	1,400	15	100	EP
тт	TTD	750	USD	1,211	13	87	AT EP SE US
UA	UAH	255	USD (or e	eq <b>UAH</b> ) 1,211	13	n a	EP RU
us	USD	300	USD	1,211	13	87	EP US
UZ	USD <sup>7</sup>	_	USD	1,211	13	87	EP RU
vc	Information no	ot yet availal	ble				
VN	VND eq USE	150	VND eq CHF 1,400		eq <b>CHF</b> 15	n a	AT AU EP KR RU SE
YU	YUD	3,000	YUD	eq <b>CHF</b> 1,400	eq <b>CHF</b> 15	eq <b>CHF</b> 100	EP
ZA	ZAR	500	ZAR	7,270	80	520	AT AU EP US
ZM	Information not yet availa		ble				
zw	<b>ZWD</b> 6,000		ZWD	eq <b>USD</b> 1,211	eq <b>USD</b> 13	eq <b>USD</b> 87	AT AU CN EP RU

**Table I(b) — Search fees** (amounts on 1 July 2005, unless otherwise indicated)

г	(amounts on 1 July 2003; unless otherwise indicated)											
ISA						Search	fee <sup>1</sup>					
AT	EUR	200	CHF	311	KRW	264,000	SGD	430	USD	262	ZAR	1,620
AU	AUD USD	1,200	CHF*	1,050	EUR */from	684	KRW	948,000	NZD	1,282	SGD	1,490
	บอบ	942	ZAR	5,800	*(from	1.6.05.	CHF	1,126)				
CA	CAD	1,600	CHF	1,520	EUR	985	USD	1,336				
CN	CNY	1,500	CHF	207	EUR	137	USD	181				
<b>EP</b> <sup>15</sup>	EUR	1,550	CAD	2,520	CHF	2,432	CYP	905	DKK	11,520	GBP	1,078
	ISK	129,000	JPY	217,300	MWK	194,000	NOK	12,650	NZD	2,884	SEK	13,870
	SGD	3,410	USD	2,075	ZAR	12,000						
<b>ES</b> <sup>15</sup>	EUR	1,550	CHF	2,432	USD	2,075						
FI	EUR	1,550	CHF	2,432	USD	2,075						
JP	JPY	97,000	CHF	1,097	EUR	692	KRW	920,000	USD	887		
KR	KRW	225,000	CHF*	238	EUR	168	NZD	315	USD	218		
	* (fro	om 1.8.05	CHF	272)								
RU <sup>16</sup>	USD	300	CHF	344	EUR	227						
SE	SEK	13,870	CHF	2,432	DKK	11,520	EUR	1,550	ISK	129,000	NOK	12,650
	USD	2,075										
US	USD ZAR	1,000 6,000	300 <sup>17</sup> 1,700 <sup>17</sup>	CHF	1,171	342 <sup>17</sup>	EUR	787	224 <sup>17</sup>	NZD	1,360	420 <sup>17</sup>

#### Table II — Preliminary examination fees

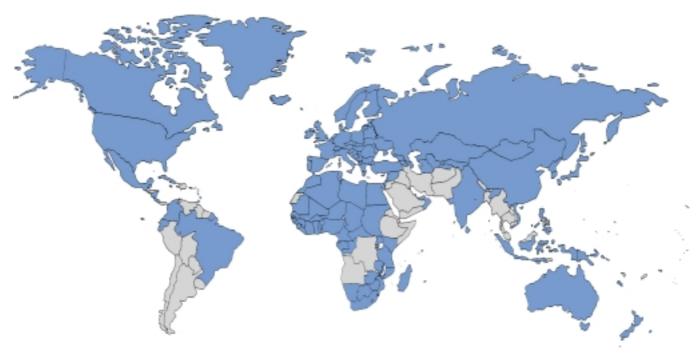
(amounts on 1 July 2005, unless otherwise indicated)

IPEA		Prelim	inary examina	tion fee <sup>18</sup>	ı	Handling fee <sup>3, 18</sup> (CHF 200)
AT	EUR	200			EUR	129
AU	AUD	550	1,000 <sup>19</sup>		AUD	218
CA	CAD	800			CAD	213
CN	CNY	1,500			CNY eq CHF	200
<b>EP</b> <sup>15</sup>	EUR	1,530			EUR	129
ES	EUR	513.03			EUR	129
FI	EUR	500	(from 15.7.05:	550)	EUR	129
JP	JPY	36,000			JPY	17,600
KR	KRW	225,000			KRW	171,000
RU <sup>16</sup>	USD	200 <sup>20</sup>	300 <sup>21</sup>		USD	173
SE	SEK	5,000			SEK	1,160
US	USD	600	750 <sup>22</sup>	_	USD	173

#### Footnotes to fee tables:

- 1 Payable to the receiving Office in the currency or one of the currencies prescribed by it.
- 2 The international filing fee is reduced by CHF 100 where: (a) the request is presented as a computer print-out prepared using the PCT-EASY features of the PCT-SAFE software; (b) the request is filed together with a computer diskette, prepared using that software, containing a copy in electronic form of the data contained in the request and of the abstract; and (c) the PCT application is filed with a receiving Office which is prepared to accept the filing of PCT applications containing requests in PCT-EASY format together with PCT-EASY diskettes.
- 3 This fee is reduced by 75% where the applicant or, if there are two or more applicants, each applicant fulfills the criteria indicated on the PCT website at: www.wipo.int/pct/en/fees/fee\_reduction.pdf
- 4 Where the PCT application as filed contains a sequence listing part in computer readable form only, or both in that form and on paper, under Section 801 of the Administrative Instructions under the PCT, and where that application is filed with a receiving Office which is prepared to accept such filings, a fixed component of 400 times the fee per sheet over 30 is payable for the sequence listing part, irrespective of the actual length of that part (see Section 803(ii) of the Administrative Instructions).
- 5 Where the international application is filed in electronic form in accordance with and to the extent provided for in Part 7 and Annex F of the Administrative Instructions and where the international application is filed with a receiving Office which has notified the International Bureau under Section 710 of the Administrative Instructions that it is prepared to receive international applications in electronic form, the international filing fee is reduced by CHF 200 if the text of the description, claims and abstract is not in character coded format, and by CHF 300 if the text of the description, claims and abstract is in character coded format. Only the following receiving Offices have sent such a notification so far: RO/EP, ES, FI, FR, GB, IB, JP, KR and NL. The equivalent amounts of those reductions in the relevant currencies are as follows: CHF 200=EUR 129, GBP 90, KRW 171,000, USD 173; CHF 300=EUR 193, GBP 134, JPY 26,400, KRW 256,000, USD 260.
- 6 For the search fee payable to the receiving Office, consult the entry in Table I(b) for the competent International Searching Authority.
- 7 The amounts are not yet known or, where known, are subject to periodical revision. The Office or the agent should be consulted for the latest applicable schedule of fees.
- 8 This fee is reduced by 80% where the applicant is a natural person.
- 9 The first amount of the transmittal fee is applicable to individuals or entities employing less than 25 persons. The second amount is applicable to entities employing 25 persons or more.
- 10 This fee is not payable in respect of international applications filed by applicants fulfilling the conditions indicated on the PCT website at: www.wipo.int/pct/en/fees/fee\_reduction.pdf
- 11 The competent International Searching Authority(ies) for an international application filed with the International Bureau as receiving Office is (are) the Authority(ies) which would have been competent if the international application had been filed with the receiving Office of, or acting for, the Contracting State of which the applicant (or any of the applicants) is a resident or national. See also *PCT Applicant's Guide*, Vol. I/B, Annex C (IB).
- 12 The Japan Patent Office is competent only for international applications in Japanese.
- 13 Plus EUR 1 for the preparation of additional copies, for each page and each copy.
- 14 Plus 12.5% GST (Goods and Services Tax) for New Zealand residents.
- 15 The search fee payable to the EPO and the Spanish Patent and Trademark Office, as well as the preliminary examination fee payable to the EPO, are reduced by 75% where the applicant or, if there are two or more applicants, each applicant is a natural person and is a national of and resides in a State not party to the European Patent Convention, which fulfils the requirements for the corresponding reduction of certain PCT fees as specified in Item 4(a) of the Schedule of Fees annexed to the PCT Regulations, and in accordance with the decision of the EPO's Administrative Council of 11 October 2000, the text of which was included in PCT Newsletter No. 11/2000. The States concerned are those indicated in part 1 of the table on the PCT website at: www.wipo.int/pct/en/fees/fee\_reduction.pdf, with the exception of Bulgaria, the Czech Republic, Estonia, Hungary, Lithuania, Poland, Romania, Slovakia and Turkey.
- 16 The applicant may, instead of paying the USD amount, pay the equivalent amount in RUR at the exchange rate applicable, on the date of payment, at the Central Bank of the Russian Federation, provided that, in the case of the search fee, the receiving Office accepts payment in RUR.
- 17 Payable when a corresponding prior US national application has been filed under 35 USC 111(a), the basic filing fee under 37 CFR 1.16(a) has been paid, and the prior US national application is identified by the application number if known, or if the application number is not known, by the filing date, title and name of applicant (and preferably by the application docket number), in the international application or accompanying the papers at the time of filing the international application.
- 18 Payable to the International Preliminary Examining Authority in the currency or one of the currencies prescribed by it.
- 19 Payable when the international search report was not issued by the Australian Patent Office.
- 20 Payable when the international search report was established by the Russian Patent Office.
- 21 In all cases where footnote 20 does not apply.
- 22 Payable when the international search was not carried out by the United States Patent and Trademark Office (USPTO) (provided that the USPTO is a competent International Preliminary Examining Authority in the particular case—see *PCT Applicant's Guide*, Vol. I/B, Annex C (US)).

## PCT Contracting States and Two-letter Codes (127 on 1 July 2005)



ΑE	United Arab		Costa Rica	IL	Israel	MK	The former		Slovakia (EP)
۸.	Emirates		Cuba (FB) <sup>2</sup>	IN	India		Yugoslav Republic		
AG	Antigua and		Cyprus (EP) <sup>2</sup>	IS	Iceland (EP)	N / I	of Macedonia <sup>1</sup>		San Marino
	Barbuda		Czech Republic (EP)	IT	Italy (EP) <sup>2</sup>		Mali (OA) <sup>2</sup>		Senegal (OA) <sup>2</sup>
	Albania <sup>1</sup>		Germany (EP)	JP	Japan (AB)		Mongolia	SY	Syrian Arab
	Armenia (EA)		Denmark (EP)	KE	Kenya (AP)		Mauritania (OA) <sup>2</sup>	07	Republic
AT	Austria (EP)		Dominica		Kyrgyzstan (EA)		Malawi (AP)		Swaziland (AP) <sup>2</sup>
ΑU			Algeria		Comoros		Mexico	TD	Chad (OA) <sup>2</sup>
ΑZ		_	Ecuador	ΚP	Democratic		Mozambique (AP)	ΤG	Togo (OA) <sup>2</sup>
BA	Bosnia and	EE	Estonia (EP)		People's Republic		Namibia (AP)	TJ.	Tajikistan (EA)
	Herzegovina <sup>1</sup>	EG	Egypt		of Korea	NE	Niger (OA) <sup>2</sup>		Turkmenistan (EA)
BB			Spain (EP)		Republic of Korea		Nigeria		Tunisia
BE	<b>3</b> \ ,	FI	Finland (EP)		Kazakhstan (EA)	NI	Nicaragua		Turkey (EP)
BF	Burkina Faso (OA) <sup>2</sup>		France (EP) <sup>2</sup>	LC	Saint Lucia	NL	Netherlands (EP) <sup>2</sup>	TT	Trinidad and Tobago
BG	Bulgaria (EP)		Gabon (OA) <sup>2</sup>	LI	Liechtenstein (EP)		Norway	ΤZ	United Republic of
BJ	Benin (OA) <sup>2</sup>		United Kingdom (EP)	LK	Sri Lanka		New Zealand		Tanzania (AP)
	Brazil		Grenada	LR	Liberia		Oman		Ukraine
	/ Botswana (AP)		Georgia	LS	Lesotho (AP)		Papua New Guinea		Uganda (AP)
BY	( )		Ghana (AP)	LT	Lithuania (EP)		Philippines	US	United States of
ΒZ			Gambia (AP)	LU	Luxembourg (EP)	PL	Poland (EP)		America
CA	Canada		Guinea (OA) <sup>2</sup>	LV	Latvia <sup>1</sup>	PT	Portugal (EP)	_	Uzbekistan
CF	00	GQ	Equatorial	LY	Libyan Arab		Romania (EP)	VC	Saint Vincent and
	Republic (OA) <sup>2</sup>		Guinea (OA) <sup>2</sup>		Jamahiriya (from	RU	Russian		the Grenadines
CG	Congo (OA) <sup>2</sup>	GR	Greece (EP) <sup>2</sup>		15 September 2005)		Federation (EA)		Viet Nam
CH	Switzerland (EP)	GW	Guinea-Bissau (OA) <sup>2</sup>	MΑ	Morocco	SC	Seychelles	YU	Serbia and
CI	Côte d'Ivoire (OA) <sup>2</sup>	HR	Croatia <sup>1</sup>	MC	Monaco (EP) <sup>2</sup>	SD	Sudan (AP)		Montenegro <sup>1</sup>
CN	Cameroon (OA) <sup>2</sup>	HU	Hungary (EP)	MD	Republic of	SE	Sweden (EP)		South Africa
	China	ID	Indonesia		Moldova (EA)	SG	Singapore		Zambia (AP)
CC	Colombia	ΙE	Ireland (EP)2	MG	Madagascar	SI	Slovenia (EP) <sup>2</sup>	ZW	Zimbabwe (AP)

Extension of European patent possible (only for international applications filed before 1 July 2005 in the case of Latvia). May only be designated for a regional patent (the "national route" via the PCT has been closed).

Where a State can be designated for a regional patent, the two-letter code for the regional patent concerned is indicated in parentheses (AP = ARIPO patent, EA = Eurasian patent, EP = European patent, OA = OAPI patent).

This list includes all States that have adhered to the PCT by the date shown in the heading. Any State indicated in **bold italics** has adhered to the PCT but will only become bound by the PCT on the date shown in parentheses; it will not be considered to have been designated in international applications filed before that date.

Note that even though the filing of a request constitutes under PCT Rule 4.9(a) the designation of all Contracting States bound by the Note that even though the filing of a request constitutes under PCT Rule 4.9(a) the designation of all Contracting States bound by the PCT on the international filing date, for the grant of every kind of protection available and, where applicable, for the grant of both regional and national patents, applicants should always use the latest versions of the request form (PCT/RO/101) and demand form (PCT/IPEA/401) (the latest versions are dated April 2005) or, if filing the request using the PCT-EASY features of the PCT-SAFE software, the latest version of that software (which is available at: www.wipo.int/pct-safe). The request and demand forms are reproduced in Annexes X and Y, respectively, in Vol. I/B of the PCT Applicant's Guide (April 2005 update), and can be printed from the WIPO Internet site, in editable PDF format, at: www.wipo.int/pct/en/forms/index.htm, or obtained from receiving Offices or the International Bureau, or, in the case of the demand form, also from International Preliminary Examining Authorities.